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Electrical conduction mechanisms in thermally evaporated tungsten trioxide (WO₃) thin films

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Abstract

Thin films of amorphous tungsten trioxide, a-WO3, have been thermally evaporated onto glass substrate held at 350 K. Annealing at 723 K caused the formation of polycrystalline tungsten trioxide, c-WO3, with a monoclinic structure. The dark DC electrical conductivity of both a-WO3 and c-WO3 was studied over a temperature range from 298 to 625 K in two environmental conditions (air and vacuum). A simple Arrhenius law, a polaron model and a variable range hopping model have been used to explain the conduction mechanism for a-WO3 films. Using the variable range hopping model, the density of localized states at the Fermi level, *N*(*E*F), was found to be $1.08 \times 10^{19} \text{ eV}^{-1} \text{ cm}^{-3}$. The mechanism of electrical conduction in c-WO3 films is explained by means of the Seto model. The Seto model parameters were determined as the energy barrier (*Eb* = 0.15 eV), the energy of trapping states with respect to the Fermi level (*Et* = 0.9 eV) and the impurity concentration (*ND* = $4.05 \times 10^{15} \text{ eV}^{-1} \text{ cm}^{-3}$). The tinckness, which is explained on the basis of the effective mean free path of electrons in c-WO3 films was evaluated. The temperature dependence of the thermoelectric power for a-WO3 films reveals that our samples are n-type semiconductors.

PACS

73.50.Pz Photoconduction and photovoltaic effects

73.50.Lw Thermoelectric effects

73.50.Gr Charge carriers: generation, recombination, lifetime, trapping, mean free paths

68.55.-a Thin film structure and morphology

73.61.Le Other inorganic semiconductors

68.55.Ln Defects and impurities: doping, implantation, distribution, concentration, etc.

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